

[DOCUMENT] ABSTRACT

The object is to provide a reflective mask blank for manufacturing a reflective mask where a shadowing effect is further reduced, which also includes an absorber film with enhanced chemical resistance.

The reflective mask blank of the present invention is a reflective mask blank including a multilayer reflective film and a thin film for pattern formation in this order on a main surface of a substrate, featured in that the thin film contains tin, tantalum, niobium, and oxygen, and the oxygen deficiency rate of the thin film is 0.15 or more and 0.28 or less.